

Recipe for photoresist AZ 1518 LSW

Application

Resist AZ1518 has an improved adhesion for wet etching.

Substrate preparation: It is preferable to process the silicon substrate by evaporation of HMDS at 150°C for 45 seconds, using the Delta RC80.

Process

Tone	Positive
Reference	Photoresist AZ 1518 Photoresists MicroChemicals GmbH
Spin coat	1,8 um @4000 RPM
Pre bake	1 min @105 °C
Exposure time HBG_uMLA	Dose 40 focus +2 @ 125mJ/cm ²
Development	30s in AZ 726 MIF
Stopping of development	30s in water then rinse it with water

Results

Spin curve

